

Amendments to the Claims:

This listing of claims replaces all prior versions, and listings, of claims in this application.

Listing of Claims:

1-11. (Canceled)

12. (Currently Amended) A multi-layered complementary wire structure, comprising:
at least one first wire extending in a first direction, the at least one first wire including:
a first main line formed in a first conductive layer; and
a plurality of first branch lines formed in a second conductive layer spaced from the first conductive layer, each of the first branch lines having a first length and being separated from an adjacent first branch line by a first distance; and
at least one second wire extending in a second direction orthogonal to the first direction, the at least one second wire including:
a second main line formed in the second conductive layer; and
a plurality of second branch lines formed in the first conductive layer, each of the second branch lines having a second length and being separated from an adjacent second branch line by a second distance,
wherein a first ratio of the first length to the first distance and a second ratio of the second length to the second distance are greater than or equal to approximately 2 in order to reduce the resistance of the multi-layered complementary wire structure.

13. (Canceled)

14. (Canceled)

15. (Previously Presented) The multi-layered complementary wire structure according to claim 12, wherein the first ratio of the first length to the first distance ranges between approximately 2 and 9.

16. (Previously Presented) The multi-layered complementary wire structure according to claim 12, wherein the second ratio of the second length to the second distance ranges between approximately 2 and 9.
17. (Previously Presented) The multi-layered complementary wire structure according to claim 12, further comprising a plurality of contact plugs for connecting the plurality of first branch lines to the first main line.
18. (Previously Presented) The multi-layered complementary wire structure according to claim 12, further comprising a plurality of contact plugs for connecting the plurality of second branch lines to the second main line.
19. (Currently Amended) A matrix structure of a display, comprising:
a substrate; and
a plurality of transistors arranged in a matrix on the substrate, each of the plurality of transistors is disposed near an intersection of a gate line extending in a first direction and a data line extending in a second direction orthogonal to the first direction and not disposed on the gate line or data line,
wherein the gate line includes:
a first main line formed in a first conductive layer; and
a plurality of first branch lines formed in a second conductive layer spaced from the first conductive layer, each of the first branch lines having a first length and being separated from an adjacent first branch line by a first distance; and
the data line includes:
a second main line formed in the second conductive layer; and
a plurality of second branch lines formed in the first conductive layer, each of the second branch lines having a second length and being separated from an adjacent second branch line by a second distance, and
wherein a first ratio of the first length to the first distance and a second ratio of the second length to the second distance are greater than or equal to approximately 2 in order to reduce the resistance of the matrix structure of the display.

20. (Canceled)
21. (Canceled)
22. (Previously Presented) The matrix structure of the display according to claim 19, wherein the first ratio of the first length to the first distance ranges between approximately 2 and 9.
23. (Previously Presented) The matrix structure of the display according to claim 19, wherein the second ratio of the second length to the second distance ranges between approximately 2 and 9.
24. (Previously Presented) The matrix structure of the display according to claim 19, further comprising a plurality of contact plugs for connecting the plurality of first branch lines to the first main line.
25. (Previously Presented) The matrix structure of the display according to claim 19, further comprising a plurality of contact plugs for connecting the plurality of second branch lines to the second main line.
26. (Currently Amended) A method for manufacturing a multi-layered complementary wire structure, comprising:
- forming a first conductive layer on a substrate;
 - patterning the first conductive layer to form a plurality of first main lines extending in a first direction and a plurality of second branch lines extending in a second direction orthogonal to the first direction, each of the plurality of second branch lines having a second length and being separated from an adjacent second branch line by a second distance;
 - forming an insulating layer on the patterned first conductive layer;
 - patterning the insulating layer to form a plurality of first contact holes exposing portions of each of the plurality of first main lines and a plurality of second contact holes exposing portions of each of the second branch lines;

forming a second conductive layer on the insulating layer to fill the first contact holes and the second contact holes; and

patterning the second conductive layer to form a plurality of second main lines extending in the second direction and a plurality of first branch lines extending in the first direction, each of the plurality of first branch lines having a first length and being separated from an adjacent first branch line by a first distance,

wherein a first ratio of the first length to the first distance and a second ratio of the second length to the second distance are greater than or equal to approximately 2 in order to reduce the resistance of the multi-layered complementary wire structure.

27. (Canceled)

28. (Canceled)

29. (Previously Presented) The method for manufacturing the multi-layered complementary wire structure according to claim 26, further comprising determining that the first ratio of the first length to the first distance ranges between approximately 2 and 9.

30. (Previously Presented) The method for manufacturing the multi-layered complementary wire structure according to claim 26, further comprising determining that the second ratio of the second length to the second distance ranges between approximately 2 and 9.